What is claimed is:

- 1. Glass-ceramics having an average linear thermal expansion coefficient within a range of $0.0\pm0.2\times10^{-7}$ °C within a temperature range from 0°C to 50°C, having difference between the maximum value and the minimum value of Δ L/L of 10×10^{-7} or below, and comprising SiO₂, Al₂O₃ and P₂O₅ with the total amount thereof in mass % being within a range from 86.0% to 89.0%.
- 2. Glass-ceramics as defined in claim 1 wherein the ratio of P_2O_5 to SiO_2 and the ratio of P_2O_5 to Al_2O_3 are

 P_2O_5/SiO_2

0.1230 - 0.1450 and

 P_2O_5/Al_2O_3

0.270 - 0.330.

- 3. Glass-ceramics having an average linear thermal expansion coefficient within a range of $0.0\pm0.1\times10^{-7}$ /°C within a temperature range from 0°C to 50°C, having difference between the maximum value and the minimum value of $\Delta L/L$ of 8×10^{-7} or below, and comprising SiO₂, Al₂O₃ and P₂O₅ with the total amount thereof in mass % being within a range from 86.0% to 89.0%.
- 4. Glass-ceramics as defined in claim 3 wherein the ratio of P_2O_5 to SiO_2 and the ratio of P_2O_5 to Al_2O_3 are

P₂O₅/SiO₂

0.1230 - 0.1450 and

 P_2O_5/Al_2O_3

0.270 - 0.330.

- 5. Glass-ceramics as defined in claim 1 wherein surface roughness (Ra) (arithmetic mean roughness) is 3 Å or below.
- 6. Glass-ceramics as defined in claim 1 wherein an average crystal grain diameter of precipitating crystal phase or phases is within a range from

50nm to 90nm.

- 7. Glass-ceramics as defined in claim 1 which comprise β -quartz (β -SiO₂) and/or β -quartz solid solution (β -SiO₂ solid solution) as a predominant crystal phase.
- 8. Glass-ceramics as defined in claim 1 which are free of PbO, Na₂O, K₂O and B_2O_3 .
- 9. Glass-ceramics as defined in claim 1 obtained by heat treating, for crystallization, a base glass which comprises, in mass %,

| SiO_2 | 53 - 57% |
|-----------------------------|----------------|
| P_2O_5 | 7.0 - 8.5% and |
| $\mathrm{Al}_2\mathrm{O}_3$ | 23 - 26% |

- 10. Glass-ceramics as defined in claim 9 comprising, in mass %, Li_2O within a range of 3.5-4.5%.
- 11. Glass-ceramics as defined in claim 10 comprising, in mass %,

| MgO | 0.5-1.5% and/or |
|----------------|-----------------|
| ZnO | 0.1-1.5% and/or |
| CaO | 0.5-1.5% and/or |
| BaO | 0.5-1.5% and/or |
| TiO_2 | 1.5-3.0% and/or |
| $ m ZrO_{2^c}$ | 1.0-3.0% and/or |
| | |

 As_2O_3 0.5 – 1.0%.

- 12. Glass-ceramics as defined in claim 1 wherein the maximum temperature of the heat treatment for crystallization is within a range from 750°C to 800°C.
- 13. A mask for lithography using glass-ceramics as defined in claim 1.
- 14. An optical system reflecting mirror for lithography using glass-ceramics as defined in claim 1.
- 15. A wafer stage or a reticle stage for lithography using glass-ceramics as defined in claim 1.
- 16. A component part of a precision instrument using glass-ceramics as defined in claim 1.
- 17. Glass-ceramics as defined in claim 3 wherein surface roughness (Ra) (arithmetic mean roughness) is 3 Å or below.
- 18. Glass-ceramics as defined in claim 3 wherein an average crystal grain diameter of precipitating crystal phase or phases is within a range from 50nm to 90nm.
- 19. Glass-ceramics as defined in claim 3 which comprise β -quartz (β -SiO₂) and/or β -quartz solid solution (β -SiO₂ solid solution) as a predominant crystal phase.
- 20. Glass-ceramics as defined in claim 3 which are free of PbO, Na₂O, K₂O

and B₂O₃.

21. Glass-ceramics as defined in claim 3 obtained by heat treating, for crystallization, a base glass which comprises, in mass %,

| SiO_2 | 53 – 57% |
|-----------------------------|----------------|
| P_2O_5 | 7.0 - 8.5% and |
| $\mathrm{Al}_2\mathrm{O}_3$ | 23 - 26% |

- 22. Glass-ceramics as defined in claim 21 comprising, in mass %, Li_2O within a range of 3.5-4.5%.
- 23. Glass-ceramics as defined in claim 22 comprising, in mass %,

| MgO | 0.5-1.5% and/or |
|-----------------------------|-----------------|
| ZnO | 0.1-1.5% and/or |
| CaO | 0.5-1/5% and/or |
| BaO | 0.5-1.5% and/or |
| TiO_2 | 1.5-3.0% and/or |
| ${ m ZrO_2}$ | 1.0-3.0% and/or |
| $\mathrm{As}_2\mathrm{O}_3$ | 0.5 - 1.0%. |

- 24. Glass-ceramics as defined in claim 3 wherein the maximum temperature of the heat treatment for crystallization is within a range from 750°C to 800°C.
- $25.\,\mathrm{A}\,\mathrm{mask}$ for lithography using glass-ceramics as defined in claim 3 .

- 26. An optical system reflecting mirror for lithography using glass-ceramics as defined in claim 3.
- 27. A wafer stage or a reticle stage for lithography using glass-ceramics as defined in claim 3.
- 28. A component part of a precision instrument using glass-ceramics as defined in claim 3.
- 29. Glass-ceramics as defined in claim 2 obtained by heat treating, for crystallization, a base glass which comprises, in mass %,

| SiO_2 | 53 - 57% |
|------------------|--------------|
| P_2O_5 | 7.0-8.5% and |
| Al_2O_3 | 23 - 26% |

- 30. Glass-ceramics as defined in claim 29 comprising, in mass %, Li_2O within a range of 3.5-4.5%.
- 31. Glass-ceramics as defined in claim 30 comprising, in mass %,

| $_{ m MgO}$ | 0.5-1.5% and/or |
|--------------|-------------------|
| ZnO | 0.1 - 1.5% and/or |
| CaO | 0.5-1.5% and/or |
| BaO | 0.5-1.5% and/or |
| ${ m TiO_2}$ | 1.5 - 3.0% and/or |
| $ m ZrO_2$ | 1.0 - 3.0% and/or |
| | |

 As_2O_3 0.5 – 1.0%.

32. Glass-ceramics as defined in claim 4 obtained by heat treating, for crystallization, a base glass which comprises, in mass %,

- 33. Glass-ceramics as defined in claim 32 comprising, in mass %, Li_2O within a range of 3.5-4.5%.
- 34. Glass-ceramics as defined in claim 33 comprising, in mass %,

| MgO | 0.5-1.5% and/or |
|------------|-----------------|
| ZnO | 0.1-1.5% and/or |
| CaO | 0.5-1.5% and/or |
| BaO | 0.5-1.5% and/or |
| TiO_2 | 1.5-3.0% and/or |
| $ m ZrO_2$ | 1.0-3.0% and/or |
| As_2O_3 | 0.5 - 1.0%. |